L Number	Hits	Search Text	DB	Time stamp
1	466	CHEN-COMINGin. WU-JUAN-YUANin.	USPAT;	2004/07/26 12:13
		WU-J-Yin. LUR-WATERin. LUR-Win.	US-PGPUB;	
·			EPO; JPO;	
			DERWENT;	
	1.550	420/5 211 212 214 216 215 2	IBM_TDB	0001/07/
2	16681	430/5,311,313,314,316,317.ccls.	USPAT;	2004/07/26 12:13
		438/296,424,427,692,697.ccls.	US-PGPUB;	
			EPO; JPO; DERWENT;	
			IBM TDB	
3	757	(active near region) near2 small\$2	USPAT;	2004/07/26 14:03
		J=,	US-PGPUB;	1 1 1, 31, 20 11.05
			EPO; JPO;	
			DERWENT	
4	767	(active near region) near2 larg\$2	USPAT;	2004/07/26 12:14
			US-PGPUB;	
			EPO; JPO;	
5	14272	stil (shallow add trough add isolation)	DERWENT	2004/07/26 12 15
	142/2	sti! (shallow adj trench adj isolation)	USPAT; US-PGPUB;	2004/07/26 12:15
			EPO; JPO;	
			DERWENT	
6	84039	trench	USPAT;	2004/07/26 12:15
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
7	23	partial adj reverse adj2 (mask active	USPAT;	2004/07/26 13:40
		photoresist)	US-PGPUB;	
			EPO; JPO; DERWENT	
8	. 60	((active near region) near2 small\$2) with	USPAT;	2004/07/26 12:17
-		((active near region) near2 larg\$2)	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
9	1597867	sio sio2 "sio.sub.2" oxide dioxide	USPAT;	2004/07/26 12:17
			US-PGPUB;	
			EPO; JPO;	
10	22	/420/E 211 212 214 216 218 2-1-	DERWENT	0004/07/05
10	22	' ' ' ' ' ' ' ' ' ' ' ' ' ' ' ' ' ' '	USPAT;	2004/07/26 12:25
		438/296,424,427,692,697.ccls.) and ((active near region) near2 small\$2) and ((active	US-PGPUB; EPO; JPO;	
		near region) near2 larg\$2)	DERWENT	
11	23693	trench with (sio sio2 "sio.sub.2" oxide	USPAT;	2004/07/26 12:25
		dioxide)	US-PGPUB;	,,
			EPO; JPO;	
			DERWENT	
12	34	(((active near region) near2 small\$2) with	USPAT;	2004/07/26 12:25
		((active near region) near2 larg\$2)) and	US-PGPUB;	
		(trench with (sio sio2 "sio.sub.2" oxide dioxide))	EPO; JPO;	
13	17	(((active near region) near2 small\$2) with	DERWENT USPAT;	2004/07/26 12:26
	1,	((active near region) near2 larg\$2)) same	US-PGPUB;	2004/07/26 12:26
		(trench with (sio sio2 "sio.sub.2" oxide	EPO; JPO;	
		dioxide))	DERWENT	
14	17	· · · · · · · · · · · · · · · · · · ·	USPAT;	2004/07/26 12:27
		((active near region) near2 larg\$2)) and	US-PGPUB;	
		(trench with (sio sio2 "sio.sub.2" oxide	EPO; JPO;	
		dioxide))) not ((((active near region) near2	DERWENT	
		small\$2) with ((active near region) near2 larg\$2)) same (trench with (sio sio2	1	
		sio.sub.2" oxide dioxide)))		
15	26	(((active near region) near2 small\$2) with	USPAT;	2004/07/26 13:21
		((active near region) near2 larg\$2)) not	US-PGPUB;	2001/01/20 13.21
		((((active near region) near2 small\$2) with	EPO; JPO;	
		((active near region) near2 larg\$2)) and	DERWENT	
		(trench with (sio sio2 "sio.sub.2" oxide		
1.0	~~	dioxide)))		
16	23	((active near region) near2 larg\$2) same	USPAT;	2004/07/26 13:22
		(sti! (shallow adj trench adj isolation))	US-PGPUB;	
			EPO; JPO;	
			DERWENT	

1546					
18	17	1546	hpcvd hdpcvd hdp-cvd	-	2004/07/26 13:24
18					
18					
18				-	
density hdp) adj ((chemical adj vapor adj deposit\$5) cvd)		0710		<u> </u>	2004/07/26 12 20
deposit\$\$) evd)	18	2749	((nigh add density add plasma) (nigh add	1	2004/07/26 13:38
1423 ((hpevd hdpevd hdp-evd) (((high ad) density) hdp) ad) ((chemical ad) vapor ad) density) hdp) usper usp				1	
1433 (hpevd hdpcvd hdp-cvd) (((high adj density) hdp) adj ((chemical adj vapor adj deposit\$5) cvd))) with (sio sio2 "sio.sub.2" oxide dioxide) 0			deposit\$5) cvd)		
1423 ((hpcvd hdpcvd hdp-cvd) (((high adi) density) hdp) adj ((chemical adj vapor adj deposit\$5) cvd) with (sio sio2 "mio.swb.2" oxide dioxide) Nemical adj vapor adj deposit\$5) cvd) with (sio sio2 "mio.swb.2" oxide density) hdp) adj ((chemical adj vapor adj deposit\$5) cvd) with (sio sio2 "mio.swb.2" oxide dioxide) Nemical adj vapor adj deposit\$5) cvd) with (sio sio2 "mio.swb.2" oxide dioxide) Nemical adj vapor adj deposit\$5) cvd) with (sio sio2 "mio.swb.2" oxide density) hdp) adj ((chemical adj vapor adj deposit\$5) cvd) with (sio sio2 "mio.swb.2" oxide density) hdp) adj ((chemical adj vapor adj deposit\$5) cvd) with (sio sio2 "mio.swb.2" oxide dioxide)) with (sio sio2 "mio.swb.2" oxide dioxide) with (sio2 sio2 "mio.swb.2" oxide dioxide) with (sio2 sio2 "mio.swb.2" oxide dioxide) with (sio2 sio2 "m				-	
density adj plasma) (high adj density) hdp adj ((chemical adj vapor adj deposits) cvd) DERNEMT 20	1.0	1422	(/hngard hdngard hdn gard) ///high adi	_	2004/07/26 12:29
adj ((chemical adj vapor adj deposit\$) cvd) SEP, JPG; With (sio sio2 "mio.swb.2" oxide dioxide) Chemical adj vapor adj deposit\$) cvd) With (alo sio2 "mio.swb.2" oxide dioxide) Chemical adj vapor adj deposit\$) cvd) With (alo sio2 "mio.swb.2" oxide dioxide) With (alo sio2 "mio.swb.2" oxide dioxide) With (sio sio2 "mio.swb.2" oxide density adj plasma) (high adj density hdp) adj (chemical adj vapor adj deposit\$) cvd) With (sio sio2 "mio.swb.2" oxide density adj plasma) (high adj density) hdp) adj ((chemical adj vapor adj deposit\$) cvd) With (sio sio2 "mio.swb.2" oxide dioxide) Septembry With (sio sio2 "mio.swb.2" oxide dioxide) With (sio sio2 "mio.swb.2" oxide d	19	1423		,	2004/07/26 13:39
11				1	
18					
density adj plasmaj (high adj density) hdp) daj ((chemical adj vapor adj deposit\$5) cvd) with (sio sio2 "sio.sub.2" oxide dioxide)) with trench ((((hpcwd hdpcvd hdp-cvd) (((high adj density) hdp) adj ((chemical adj vapor adj deposit\$5) cvd) with (sio sio2 "sio.sub.2" oxide dioxide)) with sios02 "sio.sub.2" oxide dioxide)) with trench same (partial with reverse with (mask active photoresist) with (sio sio2 "sio.sub.2" oxide dioxide)) with trench) same (partial with reverse with (mask active photoresist) with (sio sio2 "sio.sub.2" oxide dioxide)) with (sio sio2 "sio.sub.2" oxide dioxide)) with (sio sio2 "sio.sub.2" oxide dioxide)) with (sio sio2 "sio.sub.2" oxide dioxide) same (partial with reverse with (mask active photoresist) partial with reverse with (mask active photoresist) partial with reverse with (mask active photoresist) with (sio sio2 "sio.sub.2" oxide dioxide) same (partial with reverse with (mask active photoresist) uspar;	20	410		i .	2004/07/26 13:46
adj ((chemical adj vapor adj deposit\$5) cvd) Neth (sio sio2 *sio.8ub.2" oxide dioxide) With trench ((((hpcwt hdpcvd hdp-cvd) (((high adj density adj plasma) (high adj density) hdp) adj ((chemical adj vapor adj deposit\$5) cvd) WSPAT; US-PGPUB; EPO; JDO; DERWENT 2004/07/26 13:46 WSPAT; US-PGPUB; EPO; JDO; DERWENT WSPAT; US-PGPUB; EPO; JDO; DERWENT; IBM TDB WSPAT; US-PGPUB; EPO; JDO; DERWENT; ISM TDB WSPAT; US-PGPUB; EPO; JDO; DERWENT; I	20	410			2004/07/20 13:40
1 with (sio sio2 "sio.sub.2" oxide dioxide) with trench ((((hghd adj density) adj plasma) (high adj density) hdp) adj ((chemical adj vapor adj deposit55) cvd)) with (sio sio2 "sio.sub.2" oxide dioxide)) with trench) same (partial with reverse with (mask active photoresist)) (((hghd adj density) adj) adj ((chemical adj vapor adj deposit55) cvd)) with (sio sio2 "sio.sub.2" oxide dioxide)) with trench) same (partial with reverse with (mask active photoresist)) ((hemical adj vapor adj deposit55) cvd)) with (sio sio2 "sio.sub.2" oxide dioxide)) same (partial with reverse with (mask active photoresist)) partial with reverse with (mask active photoresist)) partial with reverse with (mask active photoresist)) (span; us-pcpUB; pc); JPO; pcmwmr)					
dioxide) with trench (((high adj density) hdp) add ((chemical adj vapor adj deposit\$s) cod)) with (sio sio2 "sio.sub.2" oxide dioxide)) with trench same (partial with reverse with (mask active photoresist)) (((hpcwd hdp-cvd)) (((high adj density) hdp) add ((chemical adj vapor adj deposit\$s) cod)) with (sio sio2 "sio.sub.2" oxide dioxide)) same (partial with reverse with (mask active photoresist)) partial with reverse with (mask active photoresist)) partial with reverse with (mask active photoresist)) partial with reverse with (mask active photoresist) (active near region) near2 wide USPAT; US-PGUUB; EPO, JPO, DERWENT USPAT; US-PGUB; EPO, JPO, DERWENT USPAT; US-PGUB; EPO, JPO, JPO; JPO; JPO; JPO; JPO; JPO; JPO; JPO;					
1				DEICHEIT	
density adj plasma	22	1		IICDAT.	2004/07/26 13:46
adj ((chemical adj vapor adj deposit\$5 cvd)) with (sio sio 2" sio.sub.2" oxide dioxide) with trench) same (partial with reverse with (mask active photoresist) (((high adj density) adj ((chemical adj vapor adj deposit\$5) cvd)) with (sio sio2 "sio.sub.2" oxide dioxide)) same (partial with reverse with (mask active photoresist) 0 p	22	_			2001,07,20 13.40
DERWENT DERWENT DERWENT					
dioxide) with trench same (partial with reverse with (mask active photoresist) (((high adj density adj plasma) (high adj density) hdp) adj ((chemical adj vapor adj deposit\$s) cvd)) with (sio sio2 "sio.sub.2" oxide dioxide)) same (partial with reverse with (mask active photoresist) partial with reverse with (mask active photoresist) partial with reverse with (mask active photoresist) partial with reverse with (mask active photoresist) USPAT, USPAT, USPAT, USPAT; USPAT					
Teverse with (mask active photoresist) (((hpcwd hdpcvd					
1					
density adj plasma) (high adj density) hdp) adj ((chemical adj vapor adj deposits) cvd) adj ((chemical adj vapor adj deposits) cvd)) with (sio sio2 "sio.sub.2" oxide dioxide) same (partial with reverse with (mask active photoresist) partial with reverse with (mask active photoresist) partial with reverse with (mask active photoresist) partial with reverse with (mask active photoresist) partial with reverse with (mask active photoresist) partial with reverse with (mask active photoresist) partial with reverse with (mask active photoresist) partial with reverse with (mask active USPAT; US-PGPUB; EPO, JPO; DERWENT USPAT; US-PGPUB; EPO, JPO; DERWENT; US-PGPUB; EPO, JPO; DERWENT USPAT; US-PGPUB; EPO, JPO; DERWENT;	23	Λ		USPAT:	2004/07/26 13:46
adj ((chemical adj vapor adj deposit\$5) cvd) bith (sio sio2 viso. sub.2" oxide dioxide)) same (partial with reverse with (mask active photoresist) partial with reverse with (mask active photoresist) USPAT; US-PGPUB; EPO, JPO, DERMENT 2004/07/26 14:04 USPAT; US-PGPUB; EPO, JPO; DERMENT USPAT; US-PGPUB; EPO, JPO; DERMENT; IBM TDB USPAT; US-PGPUB; EPO, JPO; DERMENT; US-PGPUB; EPO, JPO;	23	1			2001/07/20 13:10
DERWENT DERWENT DERWENT DERWENT					
dioxide) same (partial with reverse with (mask active photoresist) partial with reverse with (mask active photoresist) partial with reverse with (mask active photoresist) USPAT; US-PGPUB; EPO; JPO; DERWENT US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT; US-PGPUB; EPO					
Comparison Com	1			BERNEIVI	
21 61 partial with reverse with (mask active photoresist) 25 216 (active near region) near2 wide 26 22 (active near region) near2 dense 27 1 ((active near region) near2 wide) and ((active near region) near2 dense) 28 341 (active near region) near2 dense) 29 40 ((active near region) near2 narrow 29 40 ((active near region) near2 wide) same ((active near region) near2 narrow) 29 40 ((active near region) near2 narrow) 2004/07/26 14:04 2004/07/26 14:05 2004/07/26 14:06 2004/07/26 14:06 2004/07/26 14:06 2004/07/26 14:06 2004/07/26 14:10 2004/07/26 14:10 2004/07/26 14:11 2004/07/26 14:11 2004/07/26 14:11 2004/07/26 14:11 2004/07/26 14:12 2004/07/26 14:12 2004/07/26 14:12 2004/07/26 14:12 2004/07/26 14:12 2004/07/26 14:12 2004/07/26 14:12 2004/07/26 14:12 2004/07/26 14:12 2004/07/26 14:12 2004/07/26 14:12 2004/07/26 14:12 2004/07/26 14:12 2004/07/26 14:12					
Photoresist US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT US-PGPUB; EPO; JPO; DERWENT; IBM TDB US-PGPUB; EPO; JPO; DERWENT;	21	61		USPAT:	2004/07/26 13:46
216 (active near region) near2 wide				1	2001, 07, 20 20110
25			photoresisty		
25 216 (active near region) near2 wide					
22 (active near region) near2 dense US-PGPUB; EPO; JPO; DERWENT USPAT; USPGPUB; EPO; JPO; DERWENT; USPAT; US	25	216	(active near region) near2 wide		2004/07/26 14:04
22 (active near region) near2 dense			(, - ,
DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT; IEM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IEM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; J				· ·	
US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; USPAT; USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; US-PGPUB; EPO; JPO; DERWE					
US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; USPAT; USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; US-PGPUB; EPO; JPO; DERWE	26	22	(active near region) near2 dense	USPAT;	2004/07/26 14:05
Composition				· · · · · · · · · · · · · · · · · · ·	
1					
Continue near region near2 dense US-PGPUB; EPO; JPO; DERMENT USPAT; US-PGPUB; EPO; JPO; DERMENT; IBM TDB USPAT; US-PGPUB; EPO; JPO; DERMENT; ISPO; JPO; JPO; DERMENT; ISPO; JPO; JPO; JPO; JPO; JPO; JPO; JPO; J				1 '	
Continue near region near2 dense US-PGPUB; EPO; JPO; DERMENT USPAT; US-PGPUB; EPO; JPO; DERMENT; IBM TDB USPAT; US-PGPUB; EPO; JPO; DERMENT; ISPO; JPO; JPO; DERMENT; ISPO; JPO; JPO; JPO; JPO; JPO; JPO; JPO; J	27	1	((active near region) near2 wide) and	USPAT;	2004/07/26 14:04
28	İ			US-PGPUB;	
DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT;					
28					
US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; Chemical\$3-mechanical\$3) adj polish\$3) Chemical\$3-mechanical\$3) adj polish\$3 US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; ISPO; JPO;	28	341	(active near region) near2 narrow		2004/07/26 14:06
### 2004/07/26 14:12 ### 2004/07/26 14:12 ### 2004/07/26 14:12 ### 2004/07/26 14:12 ### 2004/07/26 14:12 ### 2004/07/26 14:12 ### 2004/07/26 14:12 ### 2004/07/26 14:12 ### 2004/07/26 14:12 ### 2004/07/26 14:12 ### 2004/07/26 14:12 ### 2004/07/26 14:12					
DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; (chemical\$3-mechanical\$3) adj polish\$3) chemical\$3-mechanical\$3-polish\$3 251052 polish\$3 DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; ISPO; JPO; DERWENT;				EPO; JPO;	
((active near region) near2 narrow) 49697 planariz\$5 planaris\$5 105 planariz\$5 planariz\$5 planaris\$5 105 planariz\$5 planariz\$5 planariz\$5 lanariz\$5 105 planariz\$5 planariz\$5 planariz\$5 105 planariz\$5 planariz\$5 planariz\$5 planariz\$5 planariz\$5 105 planariz\$5 planariz\$5 planariz\$5 planariz\$5 planariz\$5 planariz\$5 planariz\$5		1			
2004/07/26 14:11 2004/07/26 14:11 2004/07/26 14:11 2004/07/26 14:11 2004/07/26 14:11 2004/07/26 14:11 2004/07/26 14:12 2004/07/26 2004/07/26 2004/07/26 2004/07/26 2004/07/26 200	29	40		USPAT;	2004/07/26 14:06
2004/07/26 14:11 2004/07/26 14:11 2004/07/26 14:11 2004/07/26 14:11 2004/07/26 14:11 2004/07/26 14:11 2004/07/26 14:12 2004/07/26 2004/07/26 2004/07/26 2004/07/26 2004/07/26 200			((active near region) near2 narrow)	US-PGPUB;	
30 49697 planariz\$5 planaris\$5				EPO; JPO;	
US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; (Chemical\$3-mechanical\$3)) adj polish\$3) Chemical\$3-mechanical\$3-polish\$3 Chemical\$3-mechanical\$3-polish\$3 EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; US-PGPUB; EPO; JPO; DERWENT;				DERWENT	
US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; (Chemical\$3-mechanical\$3)) adj polish\$3) Chemical\$3-mechanical\$3-polish\$3 Chemical\$3-mechanical\$3-polish\$3 EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; US-PGPUB; EPO; JPO; DERWENT;	30	49697	planariz\$5 planaris\$5	USPAT;	2004/07/26 14:11
EPO; JPO; DERWENT; IBM_TDB USPAT; (chemical\$3-mechanical\$3)) adj polish\$3) USPAT; US-PGPUB; Chemical\$3-mechanical\$3-polish\$3 251052 polish\$3 251052 polish\$3 EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; US-PGPUB; EPO; JPO; DERWENT; US-PGPUB; EPO; JPO; DERWENT;					1
DERWENT; IBM_TDB USPAT; US-PGPUB; Chemical\$3-mechanical\$3) adj polish\$3 251052 polish\$3 DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; US-PGPUB; EPO; JPO; DERWENT; DERWENT;			·	EPO; JPO;	
31				DERWENT;	
(chemical\$3-mechanical\$3)) adj polish\$3) Chemical\$3-mechanical\$3-polish\$3 251052 polish\$3 251052 polish\$3 US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; DERWENT;	1			IBM_TDB	
chemical\$3-mechanical\$3-polish\$3 EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; DERWENT; DERWENT;	31	48556		USPAT;	2004/07/26 14:12
DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;				US-PGPUB;	
32			chemical\$3-mechanical\$3-polish\$3	EPO; JPO;	
32				DERWENT;	
US-PGPUB; EPO; JPO; DERWENT;				IBM_TDB	
EPO; JPO; DERWENT;	32	251052	polish\$3	USPAT;	2004/07/26 14:12
DERWENT;				US-PGPUB;	
	1			EPO; JPO;	
IBM TDB	1			DERWENT;	
				IBM_TDB	

33	283713	(planariz\$5 planaris\$5) (cmp (((chemical\$3	USPAT;	2004/07/26 14:12
	203713	adj mechanical\$3) (chemical\$3-mechanical\$3))	US-PGPUB;	
		adj polish\$3)	EPO; JPO;	
		chemical\$3-mechanical\$3-polish\$3) polish\$3	DERWENT; IBM TDB	
34	1769	((active near region) near2 small\$2)	USPAT;	2004/07/26 14:13
		((active near region) near2 larg\$2)	US-PGPUB;	
		((active near region) near2 wide) ((active	EPO; JPO;	
		near region) near2 narrow)	DERWENT; IBM TDB	
35	23	((planariz\$5 planaris\$5) (cmp (((chemical\$3	USPAT;	2004/07/26 14:14
	23	adj mechanical\$3) (chemical\$3-mechanical\$3))	US-PGPUB;	2001, 01, 20 11111
	1	adj polish\$3)	EPO; JPO;	
		chemical\$3-mechanical\$3-polish\$3) polish\$3)	DERWENT;	
		same (((active near region) near2 small\$2)	IBM_TDB	
		((active near region) near2 larg\$2) ((active near region) near2 wide) ((active		
		near region) near2 narrow)) same (sti!		
		(shallow adj trench adj isolation))		
36	144		USPAT;	2004/07/26 14:14
		<pre>adj mechanical\$3) (chemical\$3-mechanical\$3)) adj polish\$3)</pre>	US-PGPUB; EPO; JPO;	
		chemical\$3-mechanical\$3-polish\$3) polish\$3)	DERWENT;	
		and (((active near region) near2 small\$2)	IBM_TDB	
		((active near region) near2 larg\$2)		
		((active near region) near2 wide) ((active near region) near2 narrow)) and (sti!		
		(shallow adj trench adj isolation))		
37	121	f	USPAT;	2004/07/26 14:27
		(((chemical\$3 adj mechanical\$3)	US-PGPUB;	
		(chemical\$3-mechanical\$3)) adj polish\$3)	EPO; JPO;	
		chemical\$3-mechanical\$3-polish\$3) polish\$3) and (((active near region) near2 small\$2)	DERWENT; IBM TDB	
		((active near region) near2 larg\$2)		
		((active near region) near2 wide) ((active		
		near region) near2 narrow)) and (sti!		
		(shallow adj trench adj isolation))) not (((planariz\$5 planaris\$5) (cmp		
		(((chemical\$3 adj mechanical\$3)		
		(chemical\$3-mechanical\$3)) adj polish\$3)		
		chemical\$3-mechanical\$3-polish\$3) polish\$3)		
		same (((active near region) near2 small\$2) ((active near region) near2 larg\$2)		
		((active hear region) hear2 rarg\$2)		
		near region) near2 narrow)) same (sti!		
		(shallow adj trench adj isolation)))		
38	10		USPAT;	2004/07/26 14:38
		or ("6001740") or ("5880007")).PN.	US-PGPUB; EPO; JPO;	
			DERWENT	
39	0	1	USPAT;	2004/07/26 14:38
		with (mask active photoresist))	US-PGPUB;	
			EPO; JPO;	
			DERWENT	<u></u>